ABSTRACT

The present disclosure provides a gas inlet assembly, a semiconductor process chamber, and a semiconductor process method, and belongs to the technical field of semiconductor technology. The gas inlet assembly includes a gas inlet window and a switching valve plate connected to each other. The gas inlet window is provided with a first gas inlet port and a second gas inlet port. The switching valve plate is movable relative to the gas inlet window between a first position and a second position, and the switching valve plate is provided with a gas passage, the gas passage communicating with a gas outlet end of the gas inlet assembly. When the switching valve plate is at the first position, the first gas inlet port is in communication with the gas passage and the second gas inlet port is disconnected from the gas passage. When the switching valve plate is at the second position, the second gas inlet port is in communication with the gas passage and the first gas inlet port is disconnected from the gas passage. In this way, by adjusting the position of the switching valve plate, the process gas from the previous process can be directly cut off at the position of the gas inlet window, thereby preventing residual gas from the previous process from participating in the subsequent process and helping improve the process performance.